

**University of California at Berkeley**

**EE 105:**

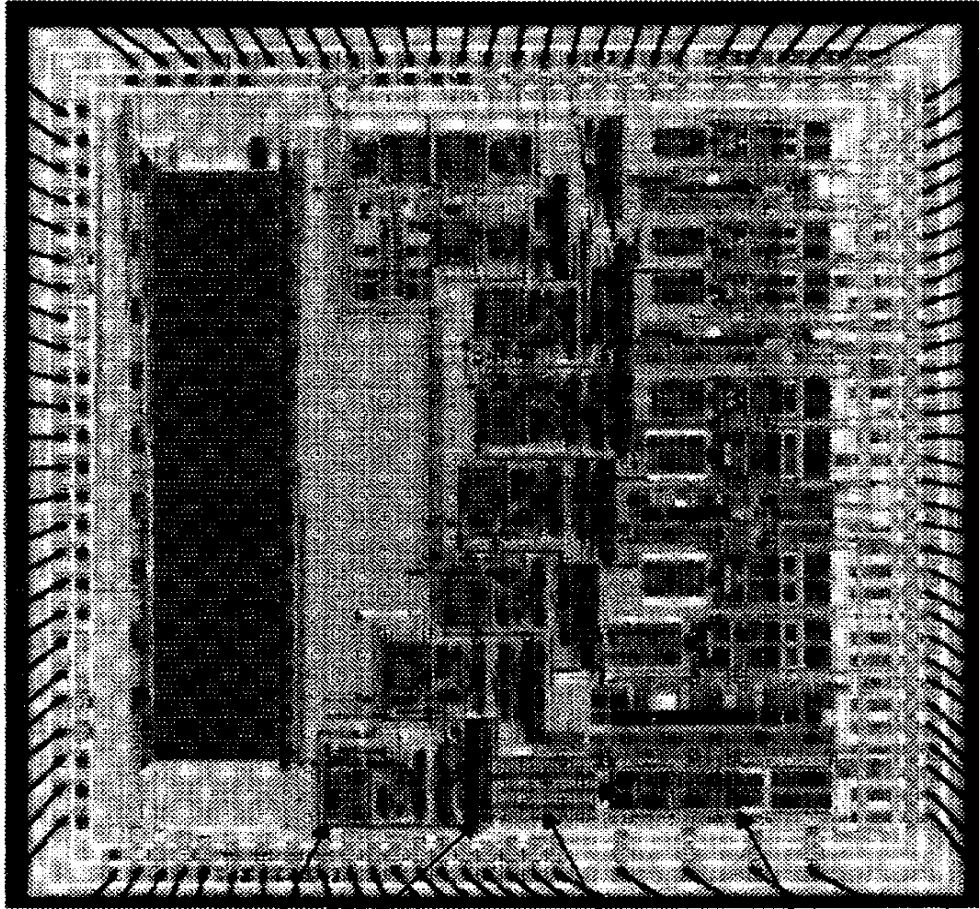
**Microelectronic Devices and Circuits**

*Spring 1997 MWF Version*

*Roger T. Howe*

## A Motivating Example

- An analog-to-digital converter for data transmission -- the analog voltage is converted into a 13 bit digital word at 5 Msamples /sec.



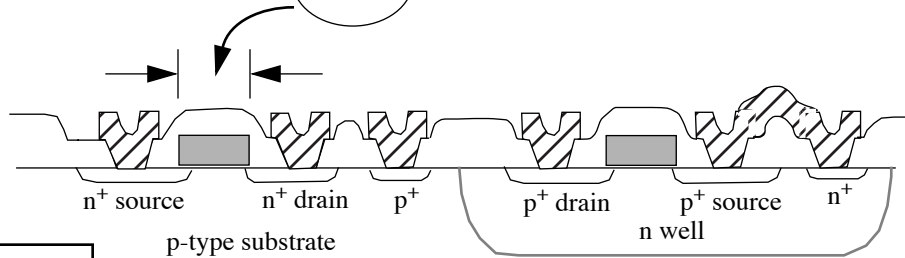
stage 0 comparators      stage 0 sampling capacitors      stage 0 opamp  
stage 0 sampling switches

Fig. 7. Die photograph of the prototype ADC.

From D. W. Cline and P. R. Gray, *IEEE J. Solid-State Circuits*, **31**, March 1996, pp. 294-303. © 1996 IEEE. Used by permission.

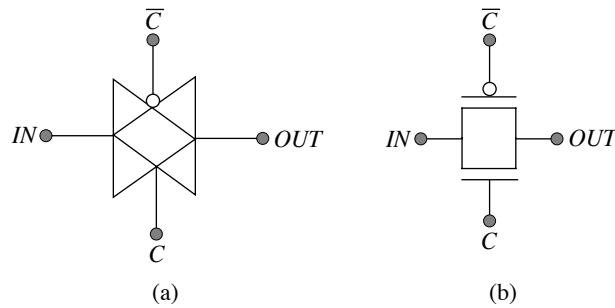
# Understanding this Microsystem on a Chip --

Technology and Devices:  $1.2\ \mu\text{m}$  n-well CMOS process



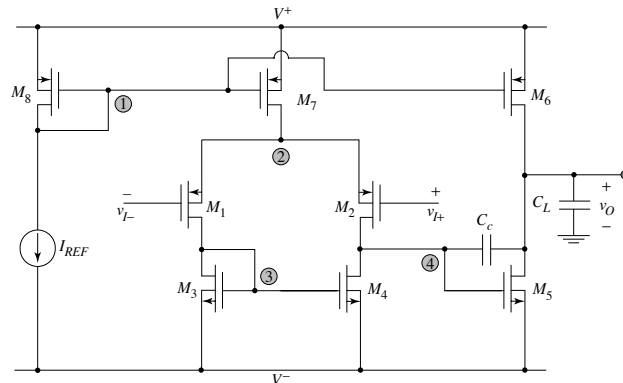
Lecture 10

Digital Integrated Circuits: switches, shift register for collecting samples



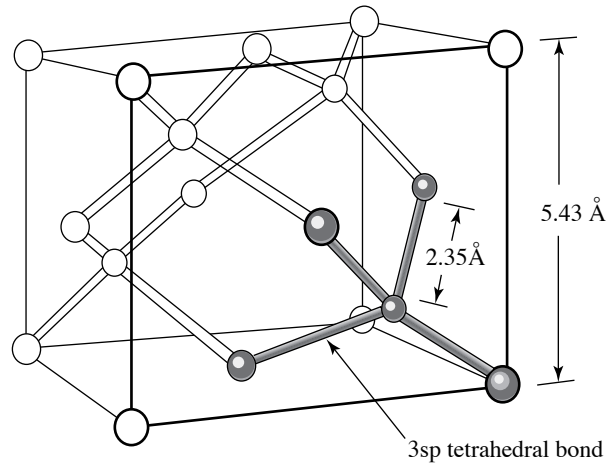
Lecture 18

Analog Integrated Circuits: 12 opertional amplifiers used in signal processing

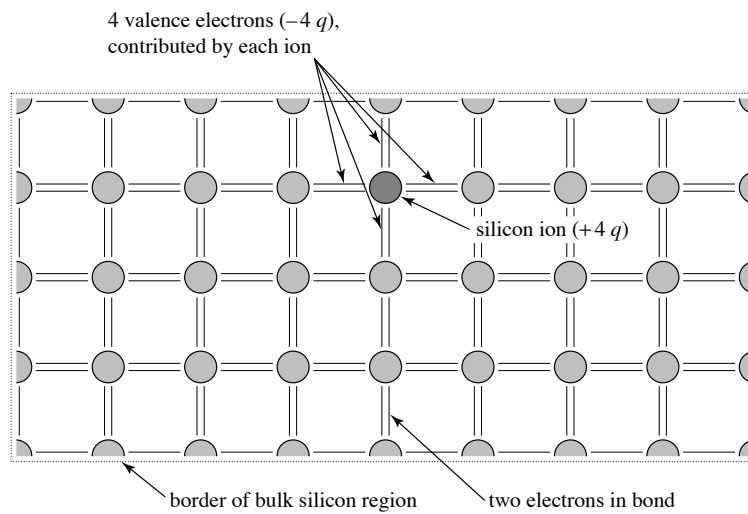


Lecture 38

# Silicon Crystal Structure

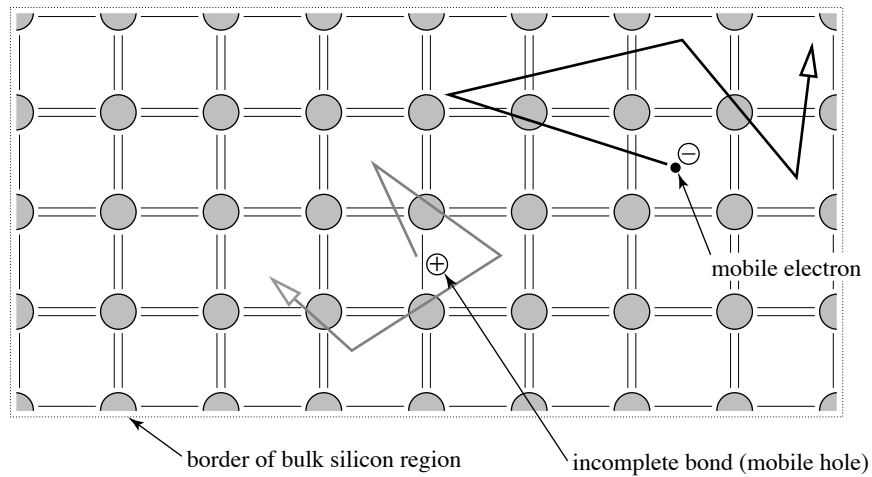


- diamond lattice
- atoms are bonded tetrahedrally with covalent bonds



- Two-dimensional crystal for sketching

## Intrinsic (Pure) Silicon ( $T > 0$ )



- electron: mobile negative unit charge, concentration  $n$  ( $\text{cm}^{-3}$ )
- hole: mobile positive unit charge, concentration  $p$  ( $\text{cm}^{-3}$ )

Unit of charge:  $q = 1.6 \times 10^{-19}$  Coulombs [C]

# Thermal Equilibrium

Generation rate:  $G$  units:  $\text{cm}^{-3} \text{s}^{-1}$  (thermal, optical processes)

Recombination rate:  $R \propto n \cdot p$

$n$  = electron concentration  $\text{cm}^{-3}$

$p$  = hole concentration  $\text{cm}^{-3}$

With the absence of external stimulus,  $G_o = R_o$

*subscript "o" indicates thermal equilibrium*

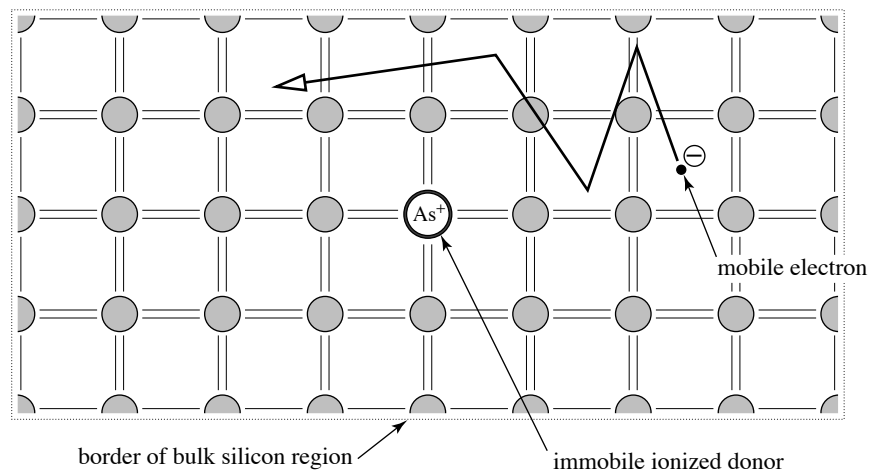
$n_o p_o = \text{constant} = n_i^2 = 10^{20} \text{cm}^{-3}$  at room temperature (approximately)

Since holes and electrons are created *together* in intrinsic silicon,

$n_o = p_o$  which implies that both are equal to  $n_i = 10^{10} \text{cm}^{-3}$

# Doping

Donors (group V) *donate* their 5<sup>th</sup> valence electron and become fixed positive charges in the lattice. Examples: Arsenic, Phosphorus.



How are the thermal equilibrium electron and hole concentrations changed by doping?

- > region is “bulk silicon” -- in the interior of the crystal, away from surfaces
- > charge in region is *zero*, before and after doping:

$$\rho = \text{charge density (C/cm}^3\text{)} = 0 = \underbrace{(-qn_o)}_{\text{electrons}} + \underbrace{(qp_o)}_{\text{holes}} + \underbrace{(qN_d)}_{\text{donors}}$$

where the donor concentration is  $N_d$  (cm<sup>-3</sup>)

## Electron Concentration in Donor-Doped Silicon

Since we are in thermal equilibrium,  $n_o p_o = n_i^2$  (not changed by doping):

Substitute  $p_o = n_i^2 / n_o$  into charge neutrality equation and find that:

$$0 = -qn_o + \frac{qn_i^2}{n_o} + qN_d$$

Quadratic formula -->

$$n_o = \frac{N_d + \sqrt{N_d^2 + 4n_i^2}}{2} = \frac{N_d}{2} + \frac{N_d}{2} \sqrt{1 + \frac{4n_i^2}{N_d^2}}$$

We *always* dope the crystal so that  $N_d \gg n_i$  ... ( $N_d = 10^{13} - 10^{19} \text{ cm}^{-3}$ ), so the square root reduces to 1:

$$n_o = N_d$$

The equilibrium hole concentration is:

$$p_o = n_i^2 / N_d$$

“one electron per donor” is a way to remember the electron concentration in silicon doped with donors.

## Numerical Example

Donor concentration:  $N_d = 10^{15} \text{ cm}^{-3}$

Thermal equilibrium electron concentration:

$$n_o \approx N_d = 10^{15} \text{ cm}^{-3}$$

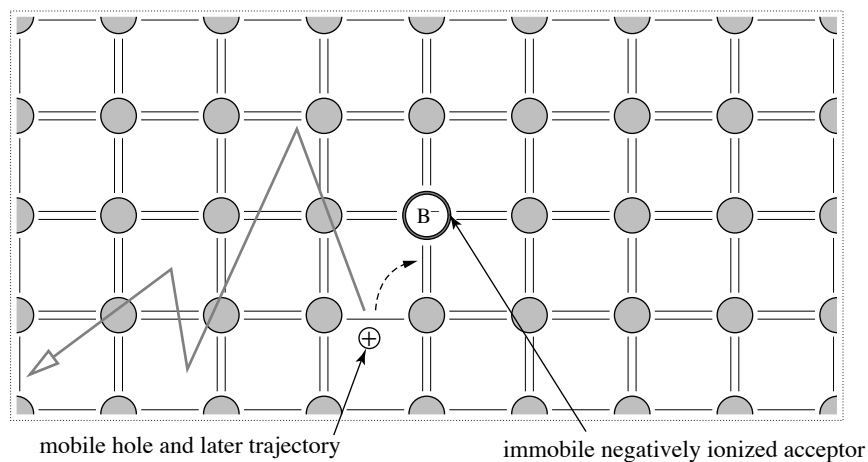
Thermal equilibrium hole concentration:

$$p_o = n_i^2 / n_o \approx n_i^2 / N_d = (10^{10} \text{ cm}^{-3})^2 / 10^{15} \text{ cm}^{-3} = 10^5 \text{ cm}^{-3}$$

Silicon doped with donors is called **n-type** and electrons are the **majority carriers**.  
Holes are the (nearly negligible) **minority carriers**.

## Doping with Acceptors

Acceptors (group III) *accept* an electron from the lattice to fill the incomplete fourth covalent bond and thereby create a mobile hole and become fixed negative charges. Example: Boron.



Acceptor concentration is  $N_a$  ( $\text{cm}^{-3}$ ), we have  $N_a \gg n_i$  typically and so:

one hole is added per acceptor:

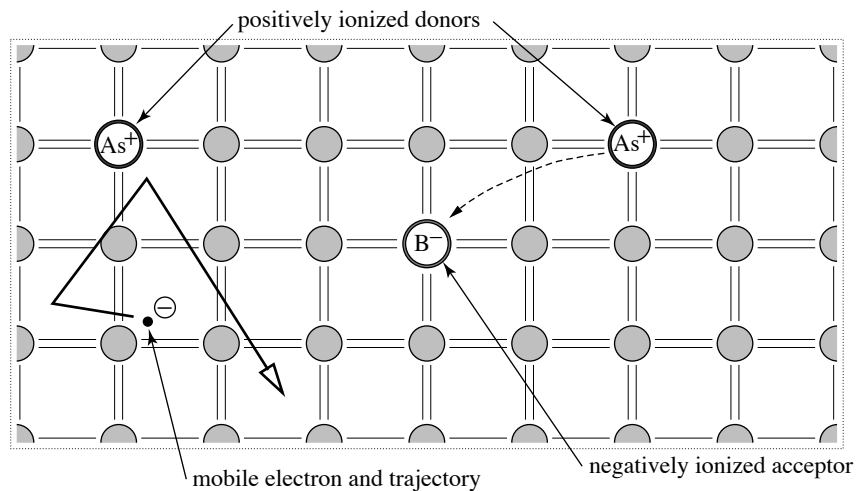
$$p_o = N_a$$

equilibrium electron concentration is::

$$n_o = n_i^2 / N_a$$

## Doping with both Donors and Acceptors: Compensation

- Typical situation is that *both* donors and acceptors are present in the silicon lattice ... mass action law means that  $n_o \neq N_d$  and  $p_o \neq N_a$  !



- Applying charge neutrality with four types of charged species:

$$\rho = -qn_o + qp_o + qN_d - qN_a = q(p_o - n_o + N_d - N_a) = 0$$

we can substitute from the mass-action law  $n_o p_o = n_i^2$  for either the electron concentration or for the hole concentration: which one is the majority carrier?

answer (not surprising):  $N_d > N_a \rightarrow$  electrons

$N_a > N_d \rightarrow$  holes

